

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it **MUST** be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Hao Tung on 26 June 2008.

The application has been amended as follows:

In the specification:

On page 1 at line 3, please replace the blank space after the words "serial no." with --10/782,545--.

In the claims:

- a. In claim 2 at line 2, please insert --(In)-- after the word "indium".
- b. In claim 2 at line 2, please delete "gallium)" and insert --gallium (Ga)-- after the word "includes".
- c. In claim 2 at line 3, please insert --, Ga,-- after "Cu, In".
- d. In claim 2 at line 3, please delete the word "liquid" and insert the word --ink-- after the words "in the".
- e. In claim 7 at line 1, please delete the word "liquid" and insert the word --suspension-- after the words "wherein the".
- f. In claim 8 at line 1, please delete the word "liquid" and insert the word --suspension-- after the words "wherein the".

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- g. In claim 34 at line 1, please delete the word "liquid" and insert the word --suspension-- after the words "wherein the".
- h. In claim 35 at line 1, please delete the word "liquid" and insert the word --suspension-- after the words "wherein the".
- i. In claim 40 at lines 4-5, please delete the phrase "one or more elements from Group IIIA in a suspension" and insert the phrase --a suspension comprising one or more elements from group IIIA-- after the word "with".
- j. In claim 40 at line 5, please delete the word "molten" and insert the word --liquid-- after the words "are in".
- k. In claim 48 at lines 1-2, please delete the phrase "a mixture of non-oxide nanoparticles" and insert the phrase -- the nanoparticles containing elements from Group IB-- after the word "forming".
- l. In claim 49 at line 1, please delete "nanoparticles in the desired size" and insert --particles in the desired particle size-- after the word "selecting".
- m. In claim 50 at line 2, please delete the word "liquid" and insert the word --suspension-- after the words "to the".
- n. In claim 51 at lines 1-2, please delete "non-oxide nanoparticles" and insert --nanoparticles containing elements from Group IB-- after the words "forming the".
- o. In claim 62, at line 3, please delete "CuIn_{1-x}Ga_x(S or Se)₂" and insert -- CuIn_{1-x}Ga_x(S or Se)₂-- after the word "approximately".

2. The following is an examiner's statement of reasons for allowance:

In addition to the reasons for indicating allowable subject matter given in the Office Action of 31 December 2007, the Examiner notes that Basol (WO 02/084708 A2; cited as Reference AV on the IDS submitted on 02 April 2008) is among the closest prior art references to the instant claims. Basol teaches deposition of a mixture of Cu and In nanoparticles in a liquid suspension onto a substrate, followed by heating at temperatures (100-300 °C) that will melt the indium particles, but not the copper particles. (Paragraphs 0035-0040) However, this melting takes place upon drying of the precursor film, and there is no disclosed step of mixing nanoparticles with a suspension comprising a liquid Group IIIA element taught or suggested by Basol. Claims 1, 13, 40, and 75 all require a step of mixing nanoparticles containing Group IB elements with a suspension comprising a metallic liquid Group IIIA based material, and these claims are therefore considered to be patentably distinguished from the prior art of record.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dr. Jeffrey T. Barton whose telephone number is (571)272-1307. The examiner can normally be reached on M-F 9:00AM - 5:30PM.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam Nguyen can be reached on (571) 272-1342. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

JTB
27 June 2008

/Alex Noguerola/
Primary Examiner, Art Unit 1795
July 7, 2008